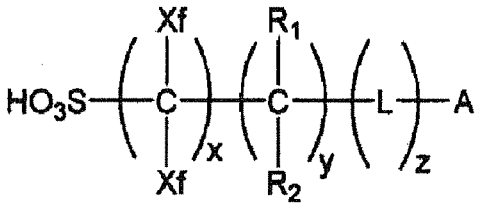
C L A I M S

1. A method of forming a pattern, comprising the step of applying an actinic-ray- or radiation-sensitive resin composition on a substrate so as to form a film, the step of selectively exposing the film through a mask and the step of developing the exposed film with the use of a developer containing an organic solvent, wherein the actinic-ray- or radiation-sensitive resin composition contains a resin (A) whose polarity is increased by the action of an acid so that the solubility of the resin in the developer containing an organic solvent is decreased, a photoacid generator (B) that when exposed to actinic rays or radiation, generates an acid containing a fluorine atom and having a cyclic structure in its molecule, and a solvent (C), and wherein the photoacid generator (B) is contained in the composition in a ratio of 8 to 20 mass% based on the total solids of the composition~~.~~, the acid generated from the photoacid generator (B) is represented by the general formula,



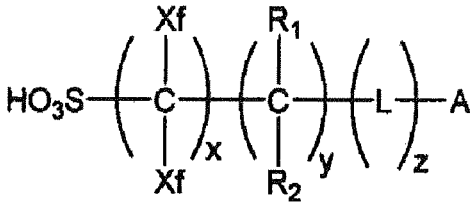
in which each of Xfs independently represents a fluorine atom or an alkyl group substituted with at least one fluorine atom; each of R^1 and R^2 independently represents a member selected from among a hydrogen

atom, a fluorine atom, an alkyl group and an alkyl group substituted with at least one fluorine atom, provided that when two or more R^1s or R^2s are contained, the two or more may be identical to or different from each other; L, each independently in the instance of Ls, represents any one of -COO-, -OCO-, -CO- and an alkylene group; A represent a group with a cyclic structure; x is an integer of 1 to 20; y is an integer of 0 to 10 and z is an integer of 0 to 10.

2. The method of forming a pattern according to claim 1, wherein the acid generated from the photoacid generator (B) contains 6 or more fluorine atoms per molecule.

3. The method of forming a pattern according to claim 1, wherein the resin (A) contains any of the repeating units of general formula (AII) below,

~~6. The method of forming a pattern according to claim 1, wherein the acid generated from the photoacid generator (B) is represented by the general formula,~~



~~in which each of Xfs independently represents a fluorine atom or an alkyl group substituted with at least one fluorine atom; each of R^1 and R^2 independently represents a member selected from among a hydrogen atom, a fluorine atom, an alkyl group and an alkyl group substituted with at least one fluorine atom, provided that when two or more R^1s or R^2s are contained, the two or more may be identical to or different from each other; L, each independently in the instance of Ls, represents a single bond or a bivalent connecting group; A represent a group with a cyclic structure; x is an integer of 1 to 20; y is an integer of 0 to 10 and z is an integer of 0 to 10.~~

~~7~~6. The method of forming a pattern according to claim 1, wherein the developer containing an organic solvent is a ketone solvent, an ester solvent or an ether solvent.

~~8~~7. The method of forming a pattern according to claim 1, wherein an ArF excimer laser is used as an exposure light source.